



<b>Session Title:</b>	<b>[TuF1] Nano Thin Film Deposition I</b>
<b>Session Date:</b>	<b>November 12 (Tue.), 2024</b>
<b>Session Time:</b>	<b>13:00-14:40</b>
<b>Session Room:</b>	<b>Room F (Ballroom, 5F, Grand Josun Busan)</b>
<b>Session Chair:</b>	<b>Prof. Woo Hee Kim (Hanyang Univ., Korea)</b>

**[TuF1-1] [Plenary] 13:00-13:45**

### **New Mechanisms for Metal Thermal Atomic Layer Etching**

Steven George (Univ. of Colorado, USA)

**[TuF1-2] [Invited] 13:45-14:15**

### **Surface Reaction Mechanisms of SiN ALD Analyzed with Atomic-Scale Simulations**

Abdullah Y. Jaber, Jomar U. Tercero, Tomoko Ito, Kazuhiro Karahashi, Kazumasa Ikuse, Michiro Isobe, and Satoshi Hamaguchi (Osaka Univ., Japan)

**[TuF1-3] [Invited] 14:15-14:40**

### **Surface Adsorption/Desorption Reactions and Precursor Design for ALD/ALE**

Sang-Ick Lee, Sangyong Jeon, Taeseok Byun, Yonghee Kwon, and Sangchan Lee (DNF Co., Ltd., Korea)